Modelling of Prompt Deposition of Tungsten under Fusion Relevant Conditions (TH/P6-22)

A. Kirschner, D. Tskhakaya, D. Borodin, S. Brezinsek, J. Romazanov, R. Ding, Ch. Linsmeier

- Modelled amount of prompt deposition with the ERO code varies from 0% to 47% for $1 \times 10^{12} \text{ cm}^{-3}$ and from 2% to 100% for $1 \times 10^{15} \text{ cm}^{-3}$.  
- For high electron density and small electron temperature: modelled mean energy of promptly deposited W significantly larger than energy from sheath field – entrainment.  
- Self-sputtering yield well below 1 for studied parameters: no runaway sputtering.